

ABSTRACT OF THE DISCLOSURE

A near-field photomask is made up of a light shield film and openings formed in the light shield. The photomask can be used to expose an exposure target with near-field light generated through the openings. The openings formed in the light shield film include two or more parallel rows of first slit openings each having a width smaller than 100 nm, and a second slit opening having a width smaller than 100 nm and extending perpendicularly to the rows of first slit openings while interlinking at least two of the rows of first slit openings.